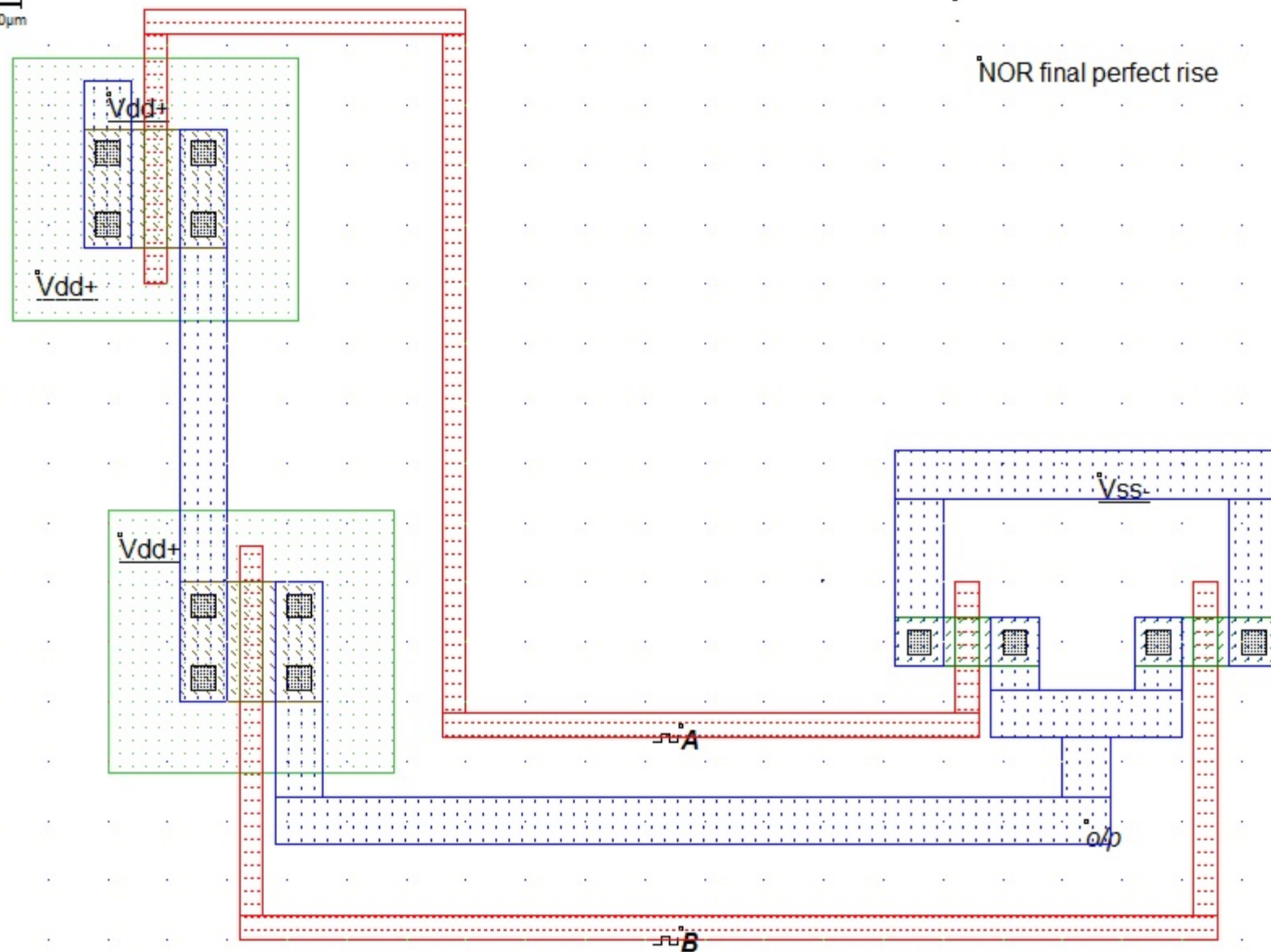


5 lambda
0.250um

Palette

Options

Metal 6

Metal 5

Metal 4

Metal 3

Metal 2

Metal 1

Polysilicon 2

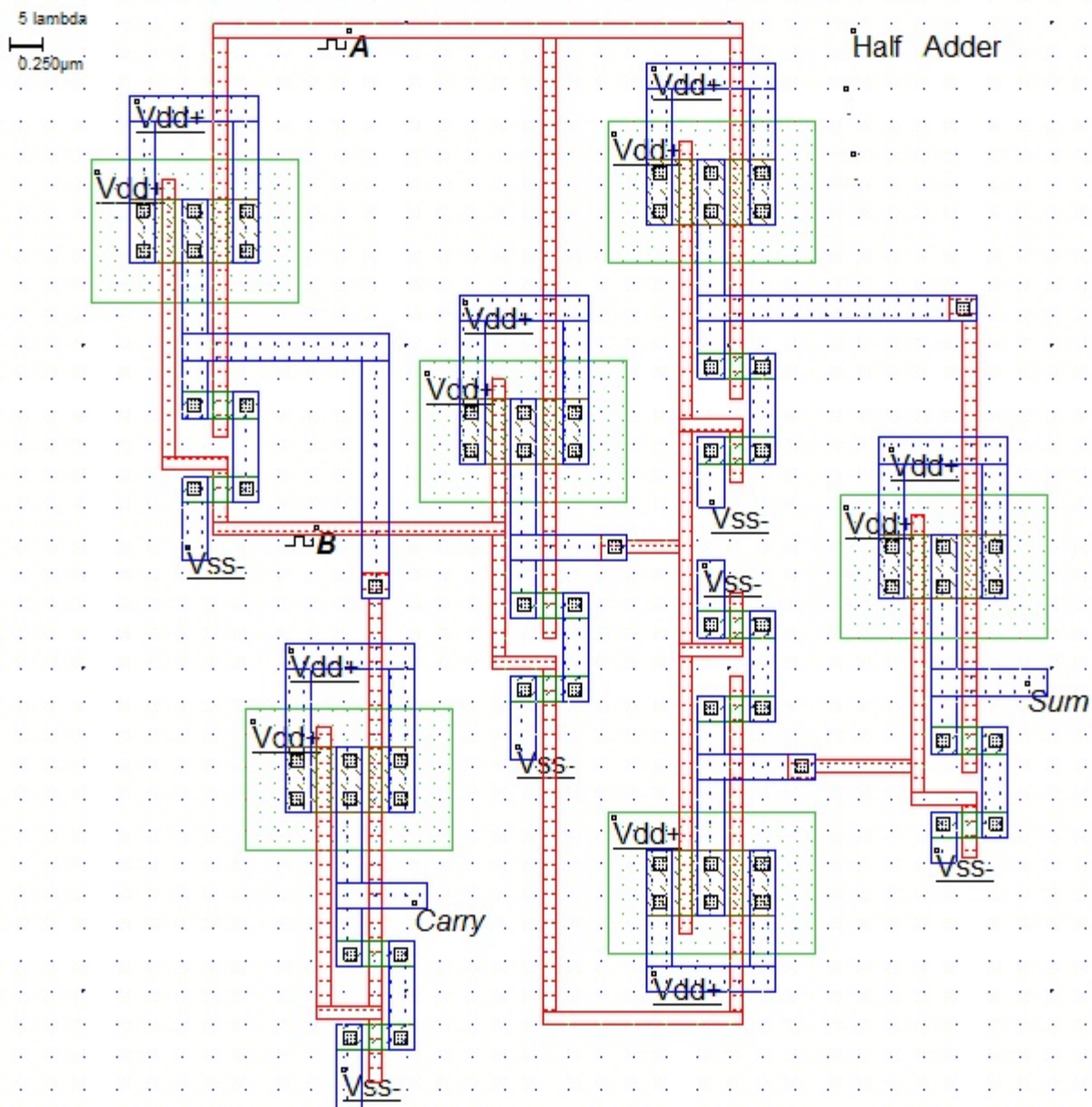
Contact

Polysilicon

P+ Diffusion

N+ Diffusion

N Well



Palette

Options

Metal 6

Metal 5

Metal 4

Metal 3

Metal 2

Metal 1

Polysilicon 2

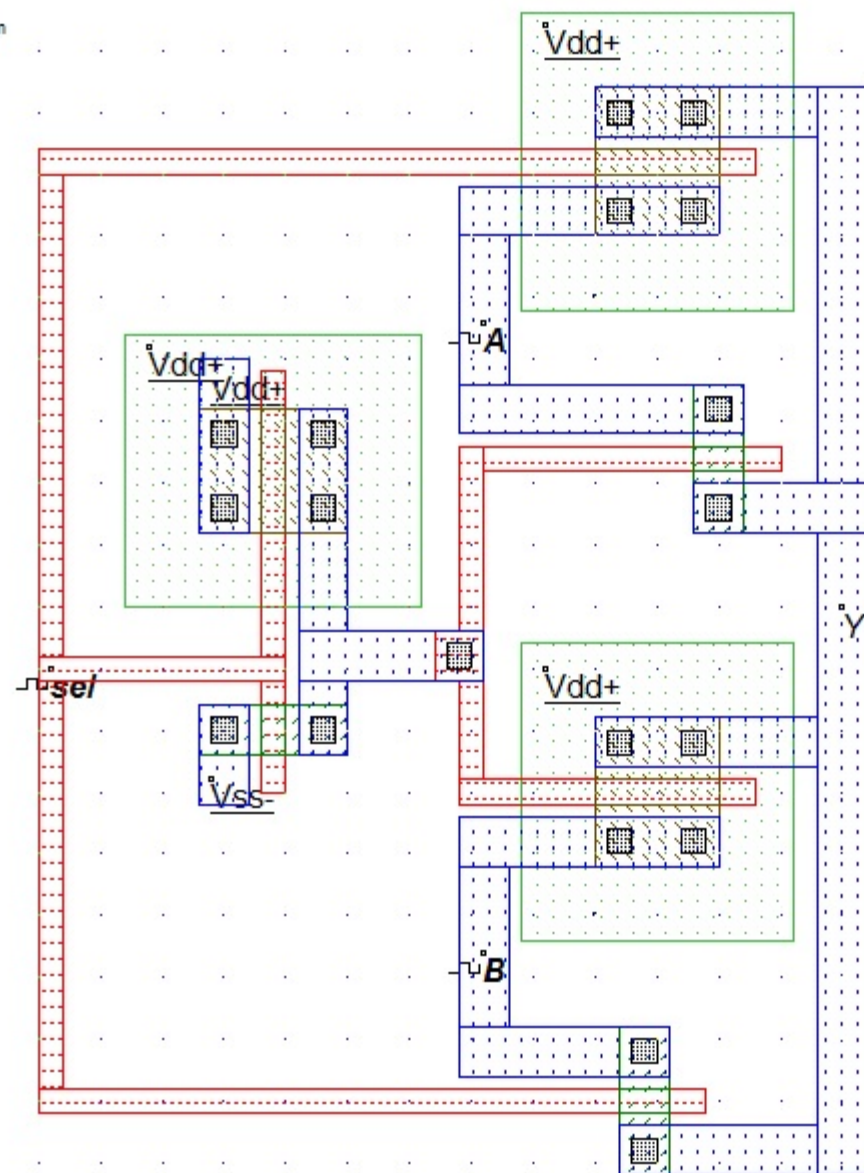
Contact

Polysilicon

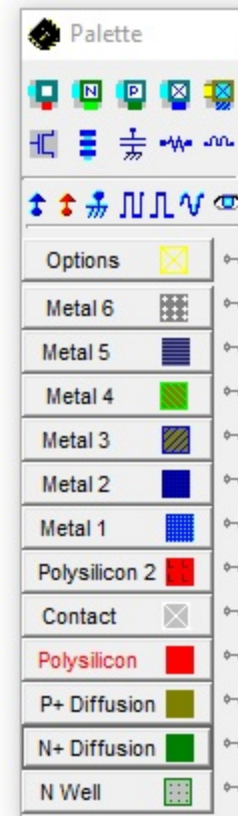
P+ Diffusion

N+ Diffusion

N Well

5 lambda
0.250µm

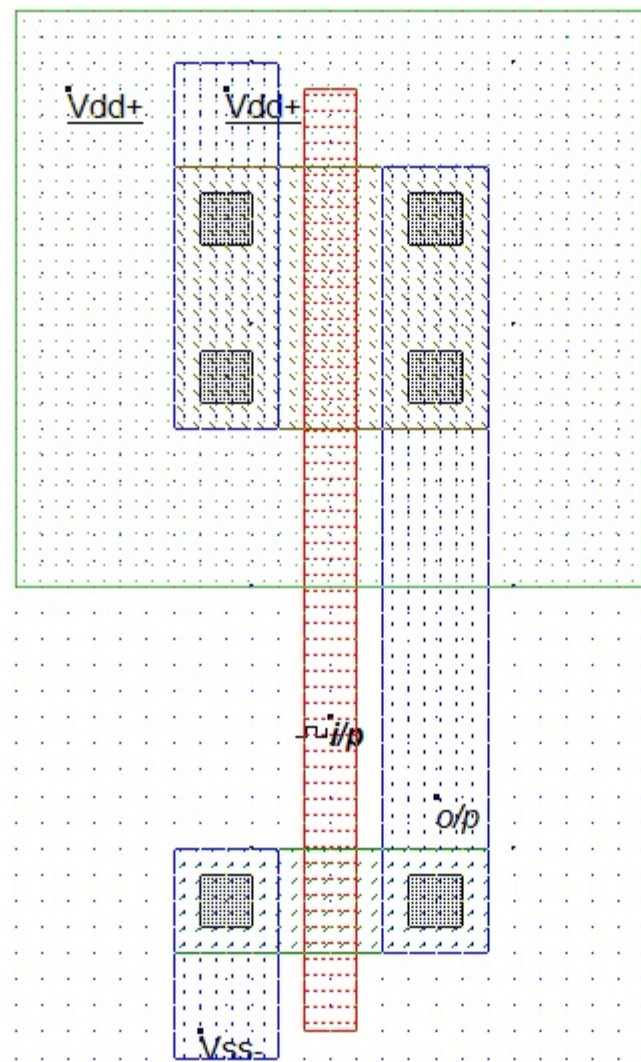
MUX using Tx Gate





1 lambda

0.050μm



Inverter with no load

Palette

Options

Metal 6

Metal 5

Metal 4

Metal 3

Metal 2

Metal 1

Polysilicon 2

Contact

Polysilicon

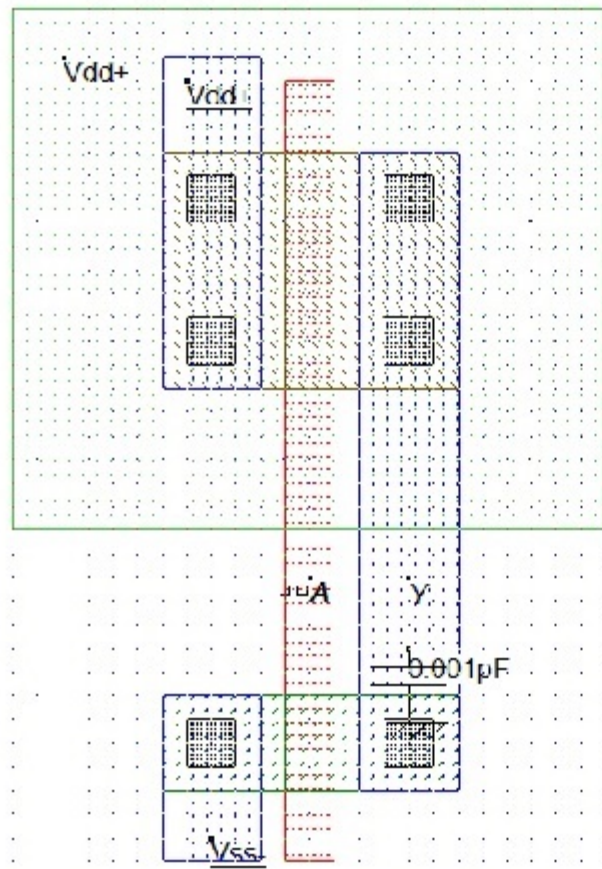
P+ Diffusion

N+ Diffusion

N Well



1 lamhda
0.050um



Inverter with C load

Options

- Metal 6
- Metal 5
- Metal 4
- Metal 3
- Metal 2
- Metal 1
- Polysilicon 2
- Contact
- Polysilicon
- P+ Diffusion
- N+ Diffusion
- N Well

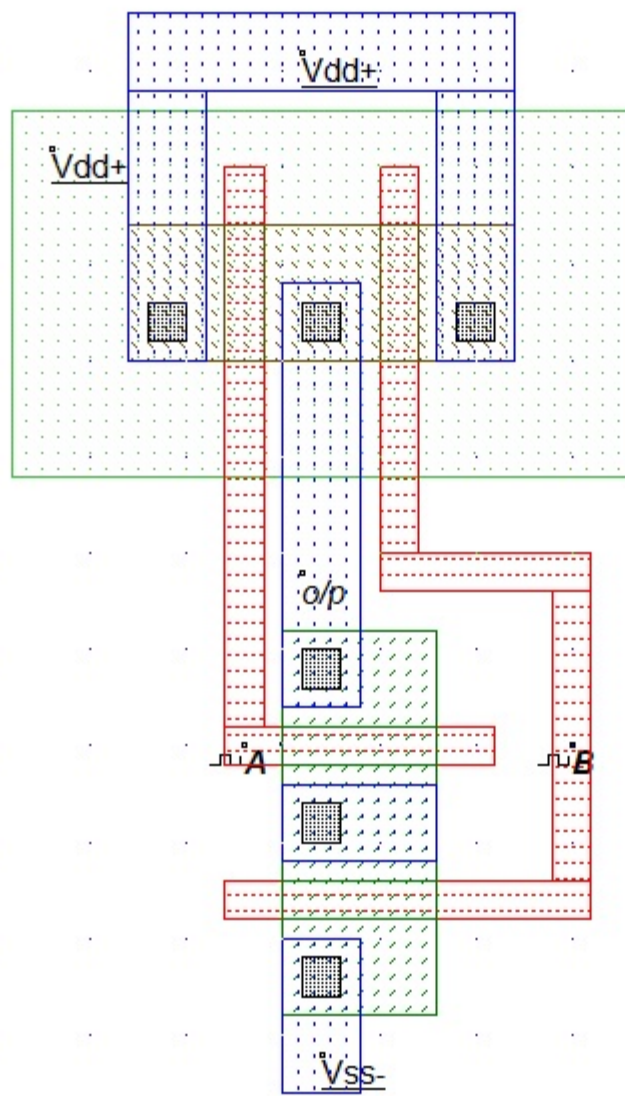
Print complete

Beta test 3.1.7 Nov 13, 2005 CMOS 90nm, 6 Metal Copper - strained SiGe - LowK (1.20V,2.50V)





5 lambda
0.250µm



NAND Gate

Palette

Options

Metal 6

Metal 5

Metal 4

Metal 3

Metal 2

Metal 1

Polysilicon 2

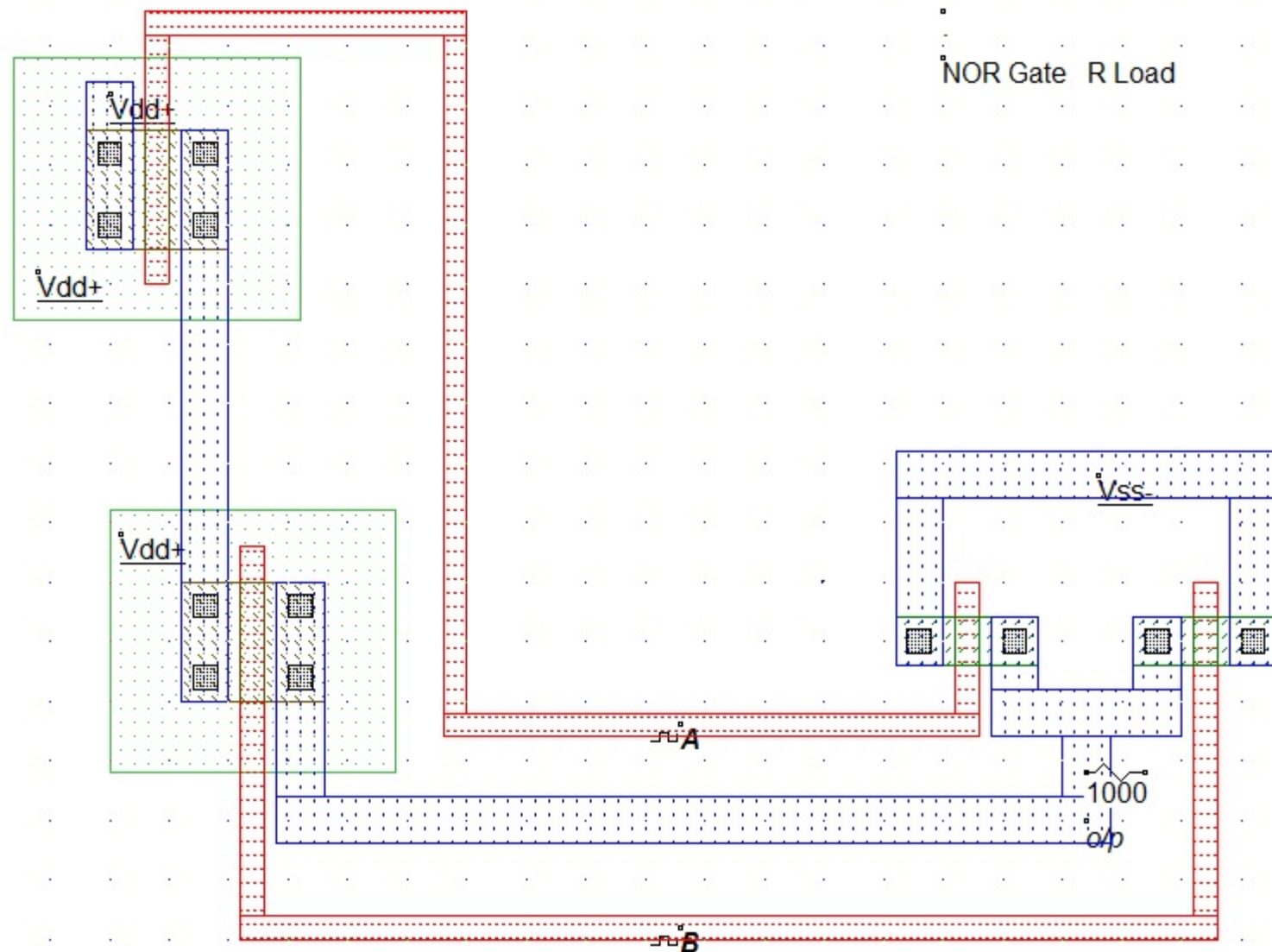
Contact

Polysilicon

P+ Diffusion

N+ Diffusion

N Well

5 lambda
0.250um

Palette

Options

Metal 6

Metal 5

Metal 4

Metal 3

Metal 2

Metal 1

Polysilicon 2

Contact

Polysilicon

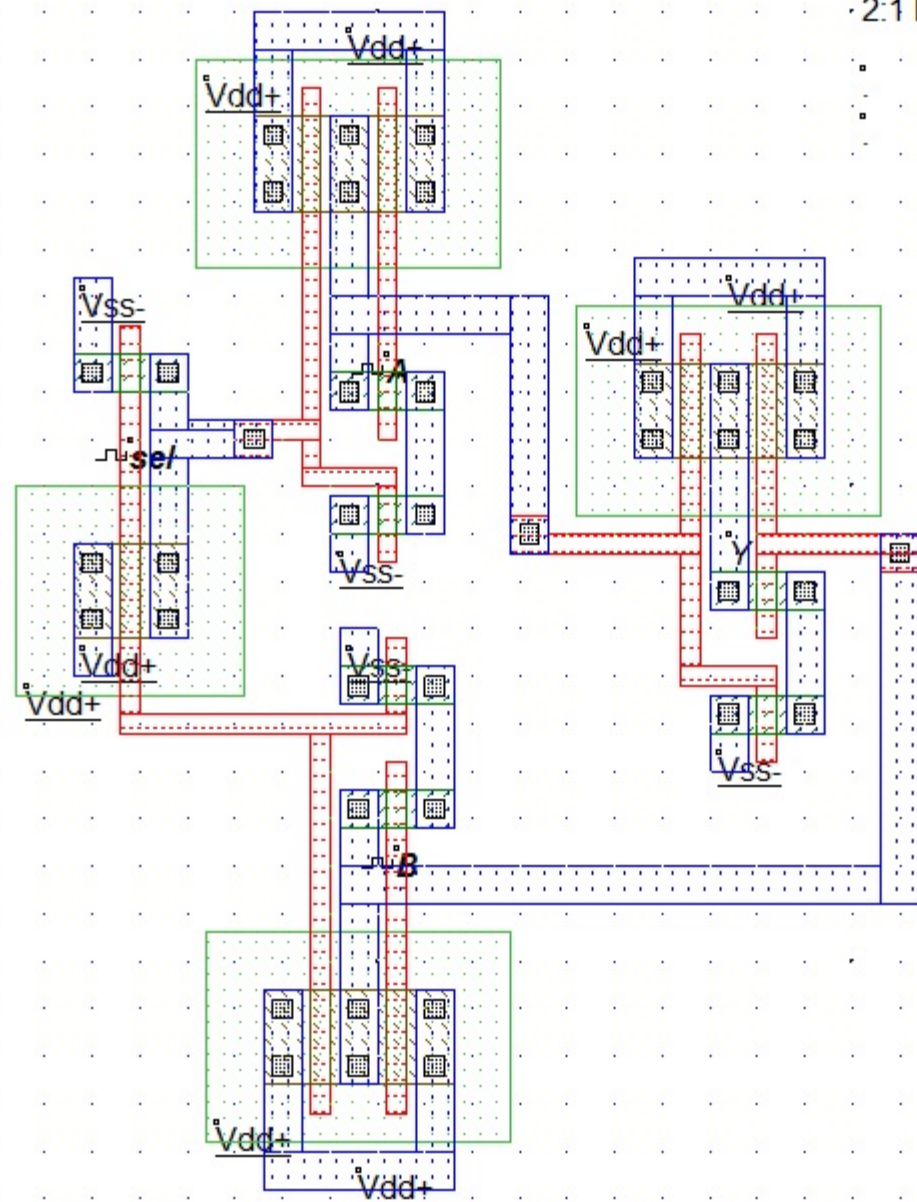
P+ Diffusion

N+ Diffusion

N Well

5 lambda
0.250µm

2:1 MUX using Gates



Palette

Options

Metal 6

Metal 5

Metal 4

Metal 3

Metal 2

Metal 1

Polysilicon 2

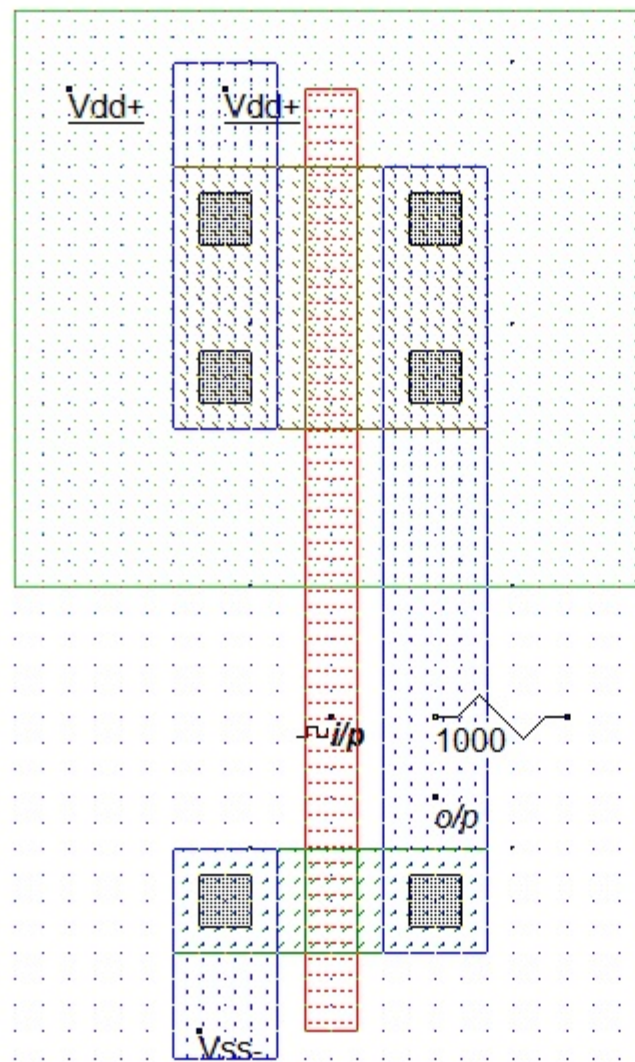
Contact

Polysilicon

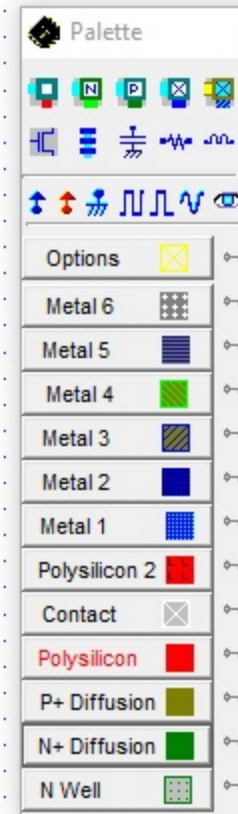
P+ Diffusion

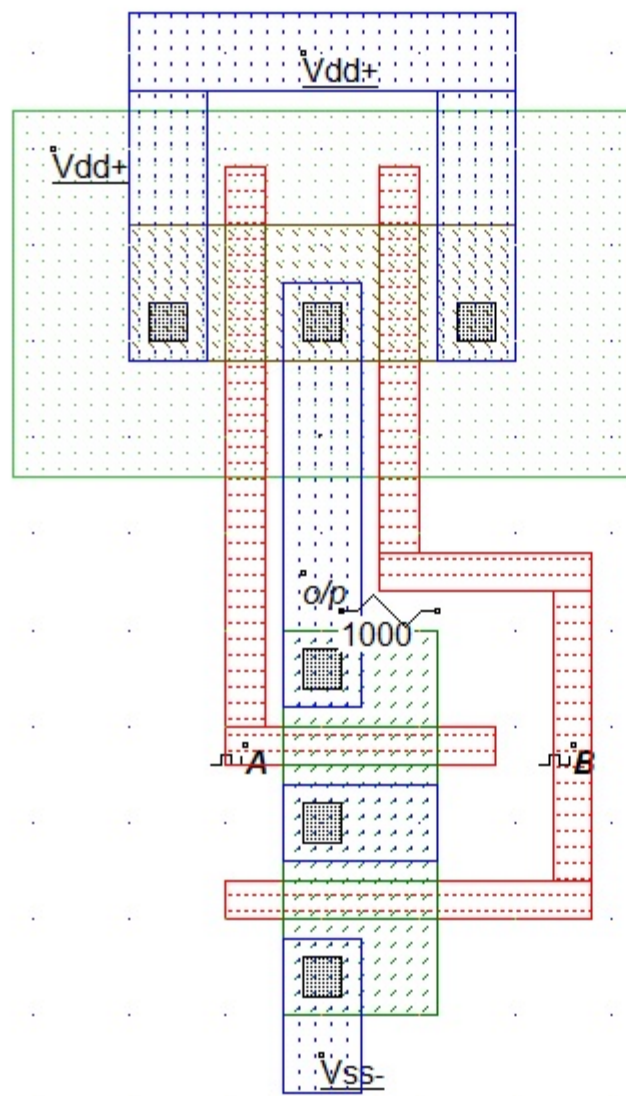
N+ Diffusion

N Well

1 lambda
0.050um

Inverter R Load



5 lambda
0.250um

NAND Gate R Load

Palette

Options

Metal 6

Metal 5

Metal 4

Metal 3

Metal 2

Metal 1

Polysilicon 2

Contact

Polysilicon

P+ Diffusion

N+ Diffusion

N Well